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=> s (settachayanon, ?)/au or (schnoes, ?)/au
             0 (SETTACHAYANON, ?)/AU
           332 (SCHNOES, ?)/AU
L1         332 (SETTACHAYANON, ?)/AU OR (SCHNOES, ?)/AU

=> s (setthachayanon, ?)/au or (schnoes, ?)/au
            13 (SETTHACHAYANON, ?)/AU
           332 (SCHNOES, ?)/AU
L2         341 (SETTHACHAYANON, ?)/AU OR (SCHNOES, ?)/AU

=> s (isocyanate1 or diisocyanate or urethane or polyurethane) and l2
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         62004 ISOCYANATE
         21037 ISOCYANATES
         70187 ISOCYANATE
                 (ISOCYANATE OR ISOCYANATES)
         45666 DIISOCYANATE
         10532 DIISOCYANATES
         49527 DIISOCYANATE
                 (DIISOCYANATE OR DIISOCYANATES)
        112922 URETHANE
          5166 URETHANES
        114520 URETHANE
                 (URETHANE OR URETHANES)
        114907 POLYURETHANE
         82962 POLYURETHANES
        137222 POLYURETHANE
                 (POLYURETHANE OR POLYURETHANES)
L3          10 (ISOCYANATE OR DIISOCYANATE OR URETHANE OR POLYURETHANE) AND L2

=> d all 1-10

L3   ANSWER 1 OF 10  CAPLUS  COPYRIGHT 2005 ACS on STN
AN   2003:1005091  CAPLUS
DN   140:10683
ED   Entered STN:  25 Dec 2003
TI   Optical article and process for forming article
IN   Dhar, Lisa; Hale, Arturo; Katz, Howard Edan; Schilling, Marcia Lea;
       ***Schnoes, Melinda Lamont***
PA   Inphase Technologies, USA
SO   U.S. Pat. Appl. Publ., 13 pp., Cont.-in-part of U.S. Ser. No. 46,822.
     CODEN: USXXCO
DT   Patent
LA   English
IC   ICM  G03H001-02
INCL 430001000; 430002000; 430290000; 430280100; 359003000
CC   74-9 (Radiation Chemistry, Photochemistry, and Photographic and Other
     Reprographic Processes)
     Section cross-reference(s): 35, 38
FAN.CNT 2
     PATENT NO.          KIND   DATE        APPLICATION NO.        DATE
     --------------      ----   --------    -------------------    --------
PI   US 2002142227        A1    20021003    US 2002-115392         20020403
     US 6939648           B2    20050906
PRAI US 1998-46822        A2    19980324
CLASS
 PATENT NO.       CLASS  PATENT FAMILY CLASSIFICATION CODES
 --------------   -----  ----------------------------------------------
 US 2002142227    ICM    G03H001-02
```

INCL 430001000; 430002000; 430290000; 430280100; 359003000
US 2002142227 NCL 430/001.000
ECLA G03F007/00B3

AB The optical article of the invention, e.g., holog. recording medium or polymeric waveguide, is formed by mixing a matrix precursor and a photoactive monomer, and curing the mixt. to form the matrix in situ. The reaction by which the matrix precursor is polymd. during the cure is independent from the reaction by which the photoactive monomer is polymd. during writing of data. In addn., the matrix polymer and the polymer resulting from polymn. of the photoactive monomer are compatible with each other. Use of a matrix precursor and photoactive monomer that polymerize by independent reactions substantially prevents cross-reaction between the photoactive monomer and the matrix precursor during the cure and inhibition of subsequent monomer polymn. Use of a matrix precursor and photoactive monomer that result in compatible polymers substantially avoids phase sepn. And in situ formation allows fabrication of articles with desirable thicknesses.

ST holog optical information storage polymer matrix

IT Polyoxyalkylenes, preparation
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(***diisocyanate*** terminated, polymer with dihydroxypolypropylene glycol and chlorophenyl acrylate, cured; holog. optical recording article and process for forming article)

IT Holography
(holog. optical recording article and process for forming article)

IT Polyoxyalkylenes, preparation
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(polymer with ***diisocyanate*** terminated polypropylene glycol and chlorophenyl acrylate, cured; holog. optical recording article and process for forming article)

IT ***Polyurethanes*** , preparation
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(polyoxyalkylene-, cross-linked; holog. optical recording article and process for forming article)

IT Information systems
(storage; holog. optical recording article and process for forming article)

IT 13633-87-9DP, 4-Chlorophenyl acrylate, polymer with ***diisocyanate*** terminated polypropylene glycol and dihydroxypolypropylene glycol, cured 25322-69-4DP, Polypropylene glycol, ***diisocyanate*** terminated, polymer with dihydroxypolypropylene glycol and chlorophenyl acrylate, cured 25322-69-4DP, Polypropylene glycol, polymer with ***diisocyanate*** terminated polypropylene glycol and chlorophenyl acrylate, cured 608525-53-7P, Pentaerythritol tetrakis(mercaptopropionate)-polypropylene glycol diglycidyl ether-styrene copolymer 608525-54-8P 608525-55-9P 608525-56-0P 608525-57-1P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(holog. optical recording article and process for forming article)

IT 90-11-9, 1-Bromonaphthalene 90-14-2, 1-Iodonaphthalene 627-31-6, 1,3-Diiodopropane 10075-72-6, 1-Methylthio naphthalene
RL: RCT (Reactant); RACT (Reactant or reagent)
(prepn. or photoactive monomer for holog. optical recording article)

IT 38066-89-6P 111220-26-9P 244301-23-3P 244301-24-4P 244301-25-5P
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(prepn. or photoactive monomer for holog. optical recording article)

L3 ANSWER 2 OF 10 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2003:972367 CAPLUS
DN 140:33675
ED Entered STN: 14 Dec 2003
TI Holographic data storage media comprising an aluminum salt compound and an asymmetric acrylate compound
IN ***Setthachayanon, Songvit*** ; Phan, Xuan T.; Michaels, Mark David; Ihas, Benjamin C.
PA Inphase Technologies, Inc., USA
SO PCT Int. Appl., 44 pp.
CODEN: PIXXD2

DT Patent
LA English
IC ICM G11C013-04
ICS G03F007-004
CC 74-8 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 2003102959	A1	20031211	WO 2003-US17011	20030529
	W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO, NZ, OM, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, UZ, VC, VN, YU, ZA, ZM, ZW				
	RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
	EP 1508144	A1	20050223	EP 2003-756276	20030529
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
PRAI	US 2002-383608P	P	20020529		
	WO 2003-US17011	W	20030529		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
WO 2003102959	ICM	G11C013-04
	ICS	G03F007-004
WO 2003102959	ECLA	G03F007/00B3; G03F007/027; G11C013/04C8

OS MARPAT 140:33675
AB A novel photoimaging system for a two-chem. system contg. liq. photoreactive asym. acrylate compd. contg. sulfur, arom. moieties, and optionally bromine, and an aluminum salt compd. is disclosed. The photoimaging system has high dynamic range (M/#) and sensitivity and unexpectedly high temp. and high humidity resistance. The photoimaging system retains its dynamic range when exposed to 60.degree.C for 4 wk while a compn. without the aluminum salt compd. lost 75% of its dynamic range under similar exposure conditions. In one embodiment, 2-10 % of a thiobutylacrylate dissolved in a two-component ***urethane*** matrix contg. 0.002-1 % of the aluminum salt compd. showed a dynamic range of greater than 5 for a 200 .mu. thick sample and retained more than 80% of the dynamic range after 4 wk exposure at 60.degree.C.
ST holog data storage media aluminum salt compd asym acrylate
IT Holographic recording materials
Optical recording
(holog. data storage media comprising aluminum salt compd. and asym. acrylate compd.)
IT 91-60-1, 2-Naphthalenethiol 106-53-6, 4-Bromophenylthiol 814-68-6, Acryloyl chloride 865-47-4
RL: RCT (Reactant); RACT (Reactant or reagent)
(holog. data storage media comprising aluminum salt compd. and asym. acrylate compd.)
IT 630131-13-4P 632331-78-3P
RL: RCT (Reactant); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); RACT (Reactant or reagent); USES (Uses)
(holog. data storage media comprising aluminum salt compd. and asym. acrylate compd.)
IT 630131-12-3P 632331-79-4P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(holog. data storage media comprising aluminum salt compd. and asym. acrylate compd.)
IT 52292-18-9, Baytec WE-180 116243-07-3, Desmodur N3200
RL: TEM (Technical or engineered material use); USES (Uses)
(holog. data storage media comprising aluminum salt compd. and asym. acrylate compd.)
RE.CNT 3 THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE

(1) Lee, C; US 5665791 A 1997 CAPLUS
(2) Lucent Technologies Inc; EP 0938027 A 1999 CAPLUS
(3) Mead Corp; EP 0435489 A 1991 CAPLUS

L3 ANSWER 3 OF 10 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2003:950572 CAPLUS
DN 140:21315
ED Entered STN: 07 Dec 2003
TI Novel exceptional high reflective index photoactive compound for optical applications
IN ***Setthachayanon, Songvit*** ; Phan, Xuan T.; Michaels, Mark David; Ihas, Benjamin C.
PA USA
SO U.S. Pat. Appl. Publ., 12 pp.
CODEN: USXXCO
DT Patent
LA English
IC ICM G03H001-04
ICS G11B007-24; G03F007-004; G03H001-10; C07C069-74; C07C319-00; C07C321-00; C07C323-00; C07C381-00
INCL 430001000; 430002000; 430270140; 430280100; 430284100; 359010000; 560001000; 568039000
CC 74-12 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2003224250	A1	20031204	US 2003-446772	20030529
WO 2003102693	A1	20031211	WO 2003-US17010	20030529

W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO, NZ, OM, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, UZ, VC, VN, YU, ZA, ZM, ZW
RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG

PRAI US 2002-383607P P 20020529
CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
US 2003224250	ICM	G03H001-04
	ICS	G11B007-24; G03F007-004; G03H001-10; C07C069-74; C07C319-00; C07C321-00; C07C323-00; C07C381-00
	INCL	430001000; 430002000; 430270140; 430280100; 430284100; 359010000; 560001000; 568039000
US 2003224250	NCL	430/001.000
	ECLA	C08F020/38; G03F007/00B3; G03F007/027
WO 2003102693	ECLA	C08F020/38; G03F007/00B3; G03F007/027

OS MARPAT 140:21315
AB A novel liq. photoreactive asym. acrylate compd. contg. sulfur, arom. moieties, and optionally bromine, and having high dynamic range sensitivity is disclosed. The acrylate compd. is a monomer for a photoimaging system. In one embodiment, when about 2-8% by wt. of the acrylate compd. is dissolved in a two-component ***urethane*** matrix system and incorporated in an optical article formed by reacting the two-component ***urethane*** matrix system, the optical article shows a sensitivity of about 4 or more and a shrinkage during the formation of the optical article of about 0.05% vs. a sensitivity of 2.26 and a shrinkage of 0.13% when tribromophenyl acrylate, a com. monomer, was used.
ST high reflective index photoactive compd holog optical recording
IT Polymerization
(cationic; prepn. of novel exceptional high reflective index photoactive compd. for holog. recording)
IT Holography
(novel exceptional high reflective index photoactive compd. for)
IT Optical recording materials
(novel exceptional high reflective index photoactive compd. for holog. recording)
IT 630131-11-2P 630131-12-3P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(novel exceptional high reflective index photoactive compd. for holog. recording)

IT 91-60-1, 2-Naphthalenethiol 106-53-6, 4-Bromophenylthiol 865-47-4 19398-47-1, 1,4-Dibromo-2-butanol
RL: RCT (Reactant); RACT (Reactant or reagent)
(prepn. of novel exceptional high reflective index photoactive compd. for holog. recording)

IT 630131-13-4P 630131-14-5P
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(prepn. of novel exceptional high reflective index photoactive compd. for holog. recording)

L3 ANSWER 4 OF 10 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2003:133327 CAPLUS
DN 138:171420
ED Entered STN: 21 Feb 2003
TI Process and composition for rapid mass production of holographic recording article from ***polyurethane*** precursors
IN ***Setthachayanon, Songvit*** ; ***Schnoes, Melinda***
PA Inphase Technologies, Inc., USA
SO PCT Int. Appl., 39 pp.
CODEN: PIXXD2
DT Patent
LA English
IC ICM C08G018-10
ICS G11B007-26; G03H001-00
CC 38-3 (Plastics Fabrication and Uses)
Section cross-reference(s): 73
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI WO 2003014178	A1	20030220	WO 2002-US24926	20020807
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, UZ, VC, VN, YU, ZA, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM				
RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
US 2003044691	A1	20030306	US 2002-146115	20020516
US 6743552	B2	20040601		
EP 1414878	A1	20040506	EP 2002-756982	20020807
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, SK				
JP 2004537620	T2	20041216	JP 2003-519124	20020807
PRAI US 2001-310225P	P	20010807		
US 2002-146115	A	20020516		
WO 2002-US24926	W	20020807		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
WO 2003014178	ICM	C08G018-10
	ICS	G11B007-26; G03H001-00
WO 2003014178	ECLA	C08G018/10+18/48; G02B006/122C; G03H001/02; G11B007/0065; G11B007/26; G11C013/04C
US 2003044691	NCL	430/001.000
	ECLA	C08G018/10+18/48; G02B006/122C; G03H001/02; G11B007/0065; G11B007/26; G11C013/04C
EP 1414878	ECLA	C08G018/10+18/48; G02B006/122C; G03H001/02; G11B007/0065; G11B007/26; G11C013/04C
JP 2004537620	FTERM	2K008/AA04; 2K008/DD12; 2K008/DD13; 2K008/FF17; 4J034/DA01; 4J034/DG04; 4J034/DG06; 4J034/HA01; 4J034/HA07; 4J034/HB08; 4J034/HC03; 4J034/HC12; 4J034/HC34; 4J034/HC35; 4J034/HC64; 4J034/HC67; 4J034/HC71; 4J034/JA42; 4J034/MA12; 4J034/MA18;

4J034/RA13; 4J034/RA16

AB An optical article comprising a photoactive material and a polymer matrix is formed by a polymg. reaction of a material comprising component 1 and component 2, component 1 comprising a NCO-terminated pre-polymer and the component 2 comprising a polyol; wherein the material has an exotherm peak occurring within 12 min after mixing the component 1 and the component 2. Rapid mass prodn. of high performance holog. recording articles is described. To prep. a high performance holog. recording article based on two-component ***urethane*** matrix system, for example, polyols and all the additives must be virtually free of moisture contents. Deaeration must be carried out, once ***isocyanate*** and polyols including catalysts and all other ingredients are mixed together, to eliminate all entrapped air that is introduced into the mixt. during mixing. The deaeration takes time, and the ***urethane*** reaction must not be allowed to take place until all air bubbles are evacuated from the ***isocyanate*** -polyols mixt. The rapid mass prodn. of this invention overcomes such process limitations and results in a high-vol. prodn. of the high performance holog. recording articles.

ST ***polyurethane*** precursor holog recording material

IT Holographic recording materials
Optical materials
Optical waveguides
Polymerization
(process and compn. for rapid mass prodn. of holog. recording article from ***polyurethane*** precursors)

IT Polyoxyalkylenes, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(triols, ***polyurethanes*** ; process and compn. for rapid mass prodn. of holog. recording article from ***polyurethane*** precursors)

IT 9048-57-1DP, Baytec MP 160, ***polyurethanes*** with polyoxypropylene triols 25190-06-1DP, Polytetramethylene glycol, ***polyurethanes*** 52292-18-9DP, Baytec WE 180, ***polyurethanes*** with polyoxypropylene triols 116243-07-3DP, Desmodur N3200, ***polyurethanes*** with polyoxypropylene triols 151438-81-2P, Mondur TD 168256-05-1DP, Mondur ML, ***polyurethanes*** with polyoxypropylene triols
RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(process and compn. for rapid mass prodn. of holog. recording article from ***polyurethane*** precursors)

IT 25322-69-4D, Polypropylene Oxide, triols, ***polyurethanes*** 52794-68-0, Tribromophenylacrylate
RL: TEM (Technical or engineered material use); USES (Uses)
(process and compn. for rapid mass prodn. of holog. recording article from ***polyurethane*** precursors)

RE.CNT 3 THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD

RE

(1) Canon; JP 02078033 A 1990 CAPLUS
(2) Dainippon Printing; JP 05323850 A 1993 CAPLUS
(3) Joseph; US 5959775 A 1999

L3 ANSWER 5 OF 10 CAPLUS COPYRIGHT 2005 ACS on STN

AN 1999:631477 CAPLUS

DN 131:250476

ED Entered STN: 06 Oct 1999

TI Optical article and process for forming article

IN Dhar, Lisa; Hale, Arturo; Katz, Howard Edan; Schilling, Marcia Lea; ***Schnoes, Melinda Lamont***

PA Lucent Technologies Inc., USA

SO Eur. Pat. Appl., 16 pp.
CODEN: EPXXDW

DT Patent

LA English

IC ICM G03F007-00
ICS G03H001-02; G03F007-20

CC 74-8 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 73

FAN.CNT 2

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI EP 945762	A1	19990929	EP 1999-302010	19990316

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO

JP 11352303 A2 19991224 JP 1999-79043 19990324

PRAI US 1998-46822 A 19980324

US 1998-208557 A 19981209

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
EP 945762	ICM	G03F007-00
	ICS	G03H001-02; G03F007-20
EP 945762	ECLA	G03F007/00B3

AB The optical article of the invention, e.g., a holog. recording medium or polymeric waveguide, is formed by mixing a matrix precursor and a photoactive monomer and curing the mixt. to form the matrix in situ. The reaction by which the matrix precursor is polymd. during the cure is independent from the reaction by which the photoactive monomer is polymd. during writing of data. In addn., the matrix polymer and the polymer resulting from polymn. of the photoactive monomer are compatible with each other. The use of a matrix precursor and a photoactive monomer that polymerize by independent reactions substantially prevents cross-reaction between the photoactive monomer and the matrix precursor during the cure and inhibition of subsequent monomer polymn. The use of a matrix precursor and a photoactive monomer that result in compatible polymers substantially avoids phase sepn. And in situ formation allows fabrication of articles with desirable thicknesses.

ST optical article independent matrix polymn monomer photopolymn; hologram independent matrix polymn monomer photopolymn

IT Polyoxyalkylenes, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(***diisocyanate*** -terminated; photopolymerizable compns. for holog. and optical article fabrication contg.)

IT Polyoxyalkylenes, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(photopolymerizable compns. for holog. and optical article fabrication contg.)

IT Holography
(photopolymerizable compns. with polymerizable matrix precursors for)

IT Optical instruments
Optical waveguides
(photopolymerizable compns. with polymerizable matrix precursors for fabrication of)

IT Photoimaging materials
(photopolymerizable; with polymerizable matrix precursors for optical article fabrication)

IT 90-72-2 100-42-5, uses 2039-82-9, 4-Bromostyrene 6674-22-2 7575-23-7, Pentaerythritoltetrakis(mercaptopropionate) 13633-87-9, 4-Chlorophenyl acrylate 25322-69-4 25322-69-4D, Polypropylene glycol, ***diisocyanate*** -terminated 26142-30-3, Polypropylene glycol diglycidyl ether 125051-32-3
RL: TEM (Technical or engineered material use); USES (Uses)
(photopolymerizable compns. for holog. and optical article fabrication contg.)

IT 10075-72-6P, 1-Methylthionaphthalene 38066-89-6P 111220-26-9P 244301-25-5P
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(prepn. and reaction in prepg. photoactive monomer for photopolymerizable compns. for holog. and optical article fabrication)

IT 244301-23-3P 244301-24-4P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(prepn. and use as photoactive monomer for photopolymerizable compns. for holog. and optical article fabrication)

IT 90-11-9, 1-Bromonaphthalene 90-14-2, 1-Iodonaphthalene 624-92-0, Dimethyl disulfide 627-31-6, 1,3-Diiodopropane 1779-49-3, Methyltriphenylphosphonium bromide
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction in prepg. photoactive monomer for photopolymerizable compns. for holog. and optical article fabrication)

RE.CNT 7 THERE ARE 7 CITED REFERENCES AVAILABLE FOR THIS RECORD

RE

(1) Du Pont; EP 0407773 A 1991

(2) Essilor Int; FR 2667073 A 1992 CAPLUS
(3) Lucent Technologies Inc; EP 0824222 A 1998 CAPLUS
(4) Masami, K; US 5665494 A 1997 CAPLUS
(5) Nihon Ita Glass Kk; JP 58163903 A 1983
(6) Nihon Ita Glass Kk; JP 59071004 A 1984
(7) Tateishi Denki Kk; JP 60072927 A 1985 CAPLUS

L3 ANSWER 6 OF 10 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1997:603219 CAPLUS
DN 127:222000
ED Entered STN: 24 Sep 1997
TI ***Polyurethane*** (meth)acrylate, its manufacture, coating compositions, and wear layers for floor coverings
IN Rosenberry, Angela S.; Rupp, Claude R.; ***Setthachayanon, Songvit***
PA Armstrong World Industries Inc, USA
SO Brit. UK Pat. Appl., 34 pp.
CODEN: BAXXDU
DT Patent
LA English
IC ICM C08G018-67
ICS C09D175-16
CC 42-10 (Coatings, Inks, and Related Products)
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	GB 2307912	A1	19970611	GB 1996-25099	19961203
	GB 2307912	B2	19991208		
	CA 2189836	AA	19970605	CA 1996-2189836	19961107
	CA 2189836	C	20040525		
	EP 783008	A2	19970709	EP 1996-118484	19961118
	EP 783008	A3	19980114		
	EP 783008	B1	20040211		
	R: BE, DE, FR, LU, NL, SE				
	US 5719227	A	19980217	US 1997-853277	19970509
	US 5843576	A	19981201	US 1997-963176	19971103
PRAI	US 1995-566545	A	19951204		
	US 1997-853277	A3	19970509		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
GB 2307912	ICM	C08G018-67
	ICS	C09D175-16
GB 2307912	ECLA	C08G018/67B4D; C08G018/67B4+18/42; C08G018/78B4F; C08G018/78B4K; C08G018/79D4; C08G018/79K; C09D175/16
EP 783008	ECLA	C08G018/67B4+18/42; C08G018/67B4D; C08G018/78B4F; C08G018/78B4K; C08G018/79D4; C08G018/79K; C09D175/16
US 5719227	NCL	524/590.000; 522/012.000; 522/021.000; 522/090.000; 522/096.000; 525/455.000; 528/075.000
	ECLA	C08G018/67B4+18/42; C08G018/78B4F; C08G018/78B4K; C08G018/79D4; C08G018/79K; C09D175/16
US 5843576	NCL	428/423.100; 522/012.000; 522/021.000; 522/090.000; 522/096.000; 524/590.000; 525/123.000; 525/455.000; 528/075.000
	ECLA	C08G018/67B4+18/42; C08G018/78B4F; C08G018/78B4K; C08G018/79D4; C08G018/79K; C09D175/16

AB The multifunctional ***polyurethane*** (meth)acrylate oligomer is made by reacting a polyisocyanate with a functionality .gtoreq.3, a polyester polyol, and a hydroxyalkyl (meth)acrylate of mol. wt. .apprx.116-600. The coating compn. preferably includes a reactive (meth)acrylate diluent and a photoinitiator. Thus, a compn. contg. SR 351 diluent 16, SR 499 diluent 10, SR 502 10, Tone M 100 32.58, 1,6-hexanediol-glycerin-phthalic anhydride copolymer 8.87, and Desmodur N 3300 22.55 parts and photoinitiator was stable (70.degree. was stable >6 mo. as liq.) and was applied onto vinyl tile base and UV cured to give a coating having good stain resistance, gloss retention and scratch resistance.

ST ***polyurethane*** acrylate coating floor covering; polyester polyol ***urethane*** acrylate coating; hydroxyalkyl acrylate ***urethane*** coating; wear layer floor covering; isocyanurate trimer ***polyurethane*** acrylate coating; biuret ***isocyanate*** ***polyurethane*** acrylate coating; branched ***polyurethane*** acrylate coating

IT ***Polyurethanes*** , uses

Polyurethanes , uses
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(polyester-, acrylates; radiation curable coatings of superior gloss retention, abrasion,and stain resistance for floor coverings)

IT Floor coverings
(radiation curable ***polyurethane*** acrylate coatings of superior gloss retention, abrasion, and stain resistance for)

IT Coating materials
(radiation-curable; radiation curable ***polyurethane*** acrylate coatings of superior gloss retention, abrasion, and stain resistance for)

IT 5124-30-1DP, Methylene bis(4-cyclohexylisocyanate), isocyanurate derivs., polymer with reactive diluent, polyester polyol, and hydroxyacrylate 15625-89-5DP, SR 351, polymer with polyester polyol, hydroxyacrylate and allophanate or isocyanurate 28961-43-5DP, Sartomer 499, polymer with polyester polyol, hydroxyacrylate and allophanate or isocyanurate 75454-89-6DP, 1,6-Hexanediol-glycerin-phthalic anhydride copolymer, polymer with reactive diluent and hydroxyacrylate and allophanate or isocyanurate 101484-78-0DP, Tone M 100, polymer with reactive diluent and polyester polyol and allophanate or isocyanurate 194798-53-3P 194798-54-4P 194798-55-5P 194798-56-6P 194798-57-7P 194798-58-8P 194798-59-9P
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(radiation curable coatings of superior gloss retention, abrasion,and stain resistance for floor coverings)

L3 ANSWER 7 OF 10 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1996:535064 CAPLUS
DN 125:224751
ED Entered STN: 07 Sep 1996
TI (Meth) acrylated aromatic polyester floor covering wear layer
IN Ehrhart, Wendell A.; ***Setthachayanon, Songvit***
PA Armstrong World Industries, Inc., USA
SO U.S., 6 pp., Cont. of U.S. Ser. No. 223, 760, abandoned.
CODEN: USXXAM
DT Patent
LA English
IC ICM C08L067-07
INCL 428482000
CC 42-11 (Coatings, Inks, and Related Products)
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 5543232	A	19960806	US 1995-418873	19950406
	US 5663003	A	19970902	US 1996-644207	19960510
	US 5891582	A	19990406	US 1997-885503	19970630
PRAI	US 1994-223760	B1	19940406		
	US 1995-418873	A1	19950406		
	US 1996-644207	A1	19960510		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
US 5543232	ICM	C08L067-07
	INCL	428482000
US 5543232	NCL	428/482.000; 525/033.000; 525/170.000
	ECLA	C09D167/07; E04F015/12
US 5663003	NCL	428/482.000; 525/010.000; 525/033.000; 525/035.000; 525/170.000
	ECLA	C09D167/07; E04F015/12
US 5891582	NCL	428/482.000; 525/010.000; 525/033.000; 525/035.000; 525/170.000
	ECLA	C09D167/07; E04F015/12

AB Title resin compn. comprises an acrylated polyester, the polyester being the reaction product of an equiv. excess of diol, e.g. 1,6-hexanediol and an arom. polycarboxylic acid or anhydride, preferably trimellitic anhydride, and includes a highly ethoxylated triacrylate (for enhanced flexibility and gloss retention). These coatings have good gloss retention and better resistance to household and other stains than com. ***urethane*** /acrylate floor coverings. PVC panels were coated with a compn. contg. 1,4-cyclohexanedicarboxylic acid-1,6-hexanediol-trimellitic

anhydride polyester acrylate (hydroxy no. 48.1) 70, SR 9035 30, methyldiethanolamine 0.23, benzophenone 3.0, 1-hydroxycyclohexylphenylketone 1.0 g, and DC-193 surfactant and were cured in 2 passes under N at 0.35 J/pass, using 200 W/in Hg vapor lamps to give films having 24 h household stain test (sum of .delta.E) 75 and 90 min modified Taber abrasion test value (gloss retention) 93%.

ST clear coat no wax resilient floor; polyester acrylate clear wear layer floor; hexanediol polyester acrylate wear layer floor; trimellitic polyester acrylate wear layer floor; stain resistant polyester coating floor; photocurable polyester acrylate clear coating

IT Floors
(wear layer for; (Meth) acrylated arom. polyester floor covering resin compn. having both good stain resistance and gloss retention)

IT Polyesters, uses
RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acrylate-terminated, (Meth) acrylated arom. polyester floor covering resin compn. having both good stain resistance and gloss retention)

IT Coating materials
(glossy, stain-resistant; (Meth) acrylated arom. polyester floor covering resin compn. having both good stain resistance and gloss retention)

IT 181782-63-8P 181782-64-9P 181782-65-0P 181782-66-1P
RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
((Meth) acrylated arom. polyester floor covering resin compn. having both good stain resistance and gloss retention)

IT 98125-30-5P, 1,6-Hexanediol-Trimellitic anhydride copolymer
126982-13-6P, 1,6-Hexanediol-Trimesic acid copolymer 181517-79-3P
181517-81-7P
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
((Meth) acrylated arom. polyester floor covering resin compn. having both good stain resistance and gloss retention)

IT 181782-67-2P 181782-68-3P 181782-69-4P 181782-70-7P
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(coating having both good stain resistance and gloss retention)

IT 9002-86-2, PVC
RL: MSC (Miscellaneous)
(floor tile; (Meth) acrylated arom. polyester floor covering resin compn. having both good stain resistance and gloss retention)

L3 ANSWER 8 OF 10 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1992:540661 CAPLUS
DN 117:140661
ED Entered STN: 04 Oct 1992
TI UV-sensitive photoimaging composition for solder mask formation
IN ***Setthachayanon, Songvit***
PA Armstrong World Industries, Inc., USA
SO U.S., 11 pp. Cont.-in-part of U.S. Ser. No. 256,638.
CODEN: USXXAM
DT Patent
LA English
IC ICM G03F007-028
ICS G03F007-033
INCL 430284000
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 5089376	A	19920218	US 1989-365328	19890613
	US 5102774	A	19920407	US 1988-256638	19881012
PRAI	US 1986-939604	B2	19861208		
	US 1987-45464	B1	19870504		
	US 1988-256638	A2	19881012		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
US 5089376	ICM	G03F007-028
	ICS	G03F007-033

INCL 430284000
US 5089376 NCL 430/284.100; 430/910.000; 522/092.000; 522/095.000; 522/096.000; 522/097.000
US 5102774 NCL 430/284.100; 522/097.000

AB A UV-sensitive photoimaging compn. for forming a solder mask comprises a polymer prepd. by condensation reaction of a ***diisocyanate*** , a hydroxyalkyl (di or tri)(meth)acrylate, and a carboxylic acid polyol, a binder resin, and a crosslinking agent, wherein the carboxylic acid polyol has the formula (OH)xZCO2H where x = an integer of 2-5; Z = a linear or branched, satd., unsatd., or arom. hydrocarbon moiety having 2-29 C atoms and a polyol and/or a dicarboxylic acid polyol can also be used as a reactant in the prepn. of the polymer.

ST solder mask UV photoimaging compn; ***diisocyanate*** polymer photosensitive solder mask

IT ***Urethane*** polymers, compounds
RL: USES (Uses)
(acrylates, carboxylated, UV-sensitive photopolymerizable compns. contg., for solder mask formation)

IT Photoimaging compositions and processes
(photopolymerizable, UV-sensitive, contg. carboxylated ***urethane*** acrylates for solder mask formation)

IT 4986-89-4, Pentaerythritol tetraacrylate 9011-13-6, Maleic anhydride-styrene copolymer 10287-53-3, Ethyl p-dimethylaminobenzoate 15625-89-5 24650-42-8, 2,2-Dimethoxy-2-phenylacetophenone 75081-21-9, Isopropylthioxanthone 129406-62-8, Novacure 3800
RL: USES (Uses)
(UV-sensitive photopolymerizable compns. contg. carboxylated ***urethane*** acrylates and, for solder mask formation)

IT 82400-41-7 118244-07-8 143385-43-7 143385-44-8 143385-45-9 143480-21-1
RL: USES (Uses)
(UV-sensitive photopolymerizable compns. contg. for solder mask formation)

L3 ANSWER 9 OF 10 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1989:25483 CAPLUS
DN 110:25483
ED Entered STN: 21 Jan 1989
TI Photocurable ***urethane*** (meth)acrylate solder resists
IN ***Setthachayanon, Songvit***
PA Armstrong World Industries, Inc., USA
SO Ger. Offen., 13 pp.
CODEN: GWXXBX
DT Patent
LA German
IC ICM C08G018-34
ICS C08L075-04; C09D003-72; C09D003-80; G03F007-10; H05K003-34
ICA C08J003-28; C09D003-74; C09D007-00; H05K003-28
ICI C08J003-24, C08L075-04
CC 42-10 (Coatings, Inks, and Related Products)
Section cross-reference(s): 74, 76

FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 3741385	A1	19880609	DE 1987-3741385	19871207
	DE 3741385	C2	19960605		
	CA 1332093	A1	19940920	CA 1987-550900	19871103
	NL 8702942	A	19880701	NL 1987-2942	19871207
	NL 190785	B	19940316		
	NL 190785	C	19940816		
	FR 2607820	A1	19880610	FR 1987-17087	19871208
	FR 2607820	B1	19940610		
	CN 87107321	A	19880622	CN 1987-107321	19871208
	CN 1031227	B	19960306		
	JP 63156870	A2	19880629	JP 1987-308828	19871208
	JP 01041185	B4	19890904		
	GB 2199335	A1	19880706	GB 1987-28631	19871208
	GB 2199335	B2	19910109		
	BR 8706609	A	19880719	BR 1987-6609	19871208
	CH 680622	A	19920930	CH 1987-4773	19871208
PRAI	US 1986-939604	A	19861208		
	US 1987-45464	A	19870504		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
DE 3741385	ICM	C08G018-34
	ICS	C08L075-04; C09D003-72; C09D003-80; G03F007-10; H05K003-34
	ICA	C08J003-28; C09D003-74; C09D007-00; H05K003-28
	ICI	C08J003-24, C08L075-04
DE 3741385	ECLA	C08F299/06; C08G018/34H; C08G018/67B4+18/08B6C; C08G018/67B4D; G03F007/035
FR 2607820	ECLA	C08F299/06; C08G018/34H; C08G018/67B4+18/08B6C; C08G018/67B4D; G03F007/035

AB The title resists, resistant to org. solvents but removable by alkalies, contain polymers prepd. from ***diisocyanates*** 30-80, carboxylic acids bearing 2-5 OH groups 5-45, and hydroxyalkyl di- or tri(meth)acrylates 5-50%. A ***polyurethane*** acrylate was prepd. from 1,6-hexanediol 4, dimethylolpropionic acid 4, 2-hydroxyethyl acrylate 8.2, and trimethylhexamethylene ***diisocyanate*** 16 equiv in 784 g N-methylpyrrolidone (I) and mixed (77.5 g) with maleic anhydride-styrene copolymer iso-Bu ester 82.0, trimethylolpropane triacrylate 47.8, isopropylthioxanthone 6.5, p-Me2NC6H4CO2Et 8.4, antifoam 6.5, phenothiazine 0.004, green dye 9.0, and I 91.25 g. This compn. was coated on a Cu-plated epoxy resin board, dried, cured through a neg. by UV, developed with 1% aq. K2CO3, cured, and post-cured to give a CH2Cl2-resistant mask resisting molten solder (260-275.degree.).

ST solder resist photocurable; ***polyurethane*** acrylate solder resist; crosslinking agent solder resist; trimethylolpropane acrylate crosslinker; developer alkali solder resist

IT ***Urethane*** polymers, uses and miscellaneous
RL: USES (Uses)
(acrylate-terminated, solder resists, photocurable and alkali-removable)

IT Resists
(photo-, solder, ***polyurethane*** acrylates as)

IT Soldering
(resists, photocurable ***polyurethane*** acrylates, alkali-removable)

IT 58206-31-8
RL: USES (Uses)
(binders, Scripset 550, for photocurable solder resists)

IT 15625-89-5, Trimethylolpropane triacrylate
RL: MOA (Modifier or additive use); USES (Uses)
(crosslinking agents, for ***polyurethane*** acrylate solder resists, photocurable and alkali-removable)

IT 4098-71-9D, polymers with polycaprolactone triol, dimethylolpropionic acid and trimethylolpropane triacrylate 4767-03-7D, polymers with IPDI, polycaprolactone triol and trimethylolpropane triacrylate 24980-41-4D, Caprolactone polymer, triol derivs., polymers with IPDI, dimethylolpropionic acid, and trimethylolpropane triacrylate 25248-42-4D, Polycaprolactone, SRU, triol derivs., polymers with IPDI, dimethylolpropionic acid, and trimethylolpropane triacrylate 118139-86-9 118244-07-8
RL: USES (Uses)
(solder resists, photocurable and alkali-removable)

L3 ANSWER 10 OF 10 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1987:534813 CAPLUS
DN 107:134813
ED Entered STN: 17 Oct 1987
TI Bicyclic acrylic monomers
IN Herweh, John Edward; Echterling, Garry Kent; ***Setthachayanon,*** *** Songvit***
PA Armstrong World Industries, Inc., USA
SO Ger. Offen., 7 pp.
CODEN: GWXXBX
DT Patent
LA German
IC ICM C07D493-08
ICS C08F020-36; C08G065-22; G03F007-10
ICA C08J003-28; C08J003-24
ICI C08G065-22, C08L071-00
CC 35-2 (Chemistry of Synthetic High Polymers)

Section cross-reference(s): 28

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 3637467	A1	19870507	DE 1986-3637467	19861104
	US 4672098	A	19870609	US 1986-912538	19861001
	CA 1256445	A1	19890627	CA 1986-520782	19861017
	NL 8602723	A	19870601	NL 1986-2723	19861029
	NL 185922	B	19900316		
	NL 185922	C	19900816		
	AU 8664651	A1	19870514	AU 1986-64651	19861103
	AU 586046	B2	19890629		
	BE 905691	A1	19870504	BE 1986-217359	19861104
	FR 2589471	A1	19870507	FR 1986-15359	19861104
	FR 2589471	B1	19900302		
	DE 3644981	C2	19900419	DE 1986-3644981	19861104
	GB 2182661	A1	19870520	GB 1986-26579	19861106
	GB 2182661	B2	19891122		
	JP 62142182	A2	19870625	JP 1986-262916	19861106
PRAI	US 1985-795523	A	19851106		
	US 1986-912538	A	19861001		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
DE 3637467	ICM	C07D493-08
	ICS	C08F020-36; C08G065-22; G03F007-10
	ICA	C08J003-28; C08J003-24
	ICI	C08G065-22, C08L071-00
US 4672098	NCL	526/268.000; 522/169.000; 549/363.000

GI

/ Structure 1 in file .gra /

AB The ***urethanes*** I (R1 = alkyl, aryl; R2 = H, Me; Z1 = hydrocarbylene; Z2 = alkylene; x = 0 or 1) are useful in the manuf. of (co)polymers. Adding 128.4 g 2-isocyanatoethyl methacrylate over 50 min to 144.2 g 1-ethyl-2,6,7-trioxabicyclo[2.2.2]octane-4-methanol and 1.4 g triethylenediamine in C6H6, adding 0.1 g hydroquinone, and heating 4 h at 45-55.degree. gave 262.3 g ***urethane*** . AIBN-initiated photopolymn. of an 8.6% C6H6 soln. of this ***urethane*** gave a polymer (via the double bond only) with mol. wt. 50,532 (161,196 cor.) and glass temp. 84-99.degree..

ST trioxatricycloolctanemethanol ***urethane*** methacrylate; ortho ester ***urethane*** methacrylate; isocyanatoethyl methacrylate reaction alc

IT 110259-22-8P 110259-23-9P 110415-25-3P
RL: IMF (Industrial manufacture); PRP (Properties); PREP (Preparation)
(manuf. and properties of)

IT 110259-21-7P 110306-19-9P 110321-56-7P
RL: PREP (Preparation)
(prepn. of)

IT 26471-62-5, TDI
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with Et trioxabicyclooctanemethanol and hydroxyethyl acrylate)

IT 4098-71-9
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with Et trioxabicyclooctanemethanol and hydroxyethyl acrylate s)

IT 30674-80-7, Isocyanatoethylmethacrylate
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with Et trioxobicyclooctanemethanol)

IT 818-61-1
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with ***diisocyanates*** and Et trioxabicyclooctanemethanol e)

IT 74358-92-2
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with isocyanatoethyl methacrylate)

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     (FILE 'HOME' ENTERED AT 08:21:50 ON 20 SEP 2005)

     FILE 'CAPLUS' ENTERED AT 08:21:55 ON 20 SEP 2005
L1           332 S (SETTACHAYANON, ?)/AU OR (SCHNOES, ?)/AU
L2           341 S (SETTHACHAYANON, ?)/AU OR (SCHNOES, ?)/AU
L3            10 S (ISOCYANATE OR DIISOCYANATE OR URETHANE OR POLYURETHANE) AND

=> log y
COST IN U.S. DOLLARS                                SINCE FILE      TOTAL
                                                       ENTRY    SESSION
FULL ESTIMATED COST                                    46.62      46.83

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)          SINCE FILE      TOTAL
                                                       ENTRY    SESSION
CA SUBSCRIBER PRICE                                    -7.30      -7.30

STN INTERNATIONAL LOGOFF AT 08:24:01 ON 20 SEP 2005
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